

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	NINISTÖ et al.)	Group Art Unit: Unknown
Appl. No.	:	Not yet assigned)	
Filed	:	Herewith)	
For	:	METHOD OF DEPOSITING RARE EARTH OXIDE THIN FILMS)	
Examiner	:	Unknown)	

PRELIMINARY AMENDMENT

UNITED STATES PATENT AND TRADEMARK OFFICE
P.O. Box 2327
Arlington, VA 22202

Dear Sir:

Prior to examination on the merits, please amend the above-identified application as follows.

In the Claims:

Please replace claims 12 and 13 with the following replacement claims:

12. (Amended) A process according to claim 1, characterized in that the substrate is a silicon wafer or soda lime glass.

13. (Amended) A process according to claim 1, characterized in that the substrate is a compound semiconductor

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REMARKS

The specific changes to the claims are identified on the attached page that is captioned **"VERSION WITH MARKINGS TO SHOW CHANGES MADE."** Deletions are struck through.

Applicant submits that the present application is in condition for examination on the merits and respectfully requests the same.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: February 4, 2002

By: 

Adeel S. Akhtar
Registration No. 41,394
Attorney of Record
620 Newport Center Drive
Sixteenth Floor
Newport Beach, CA 92660
(415) 954-4114

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VERSION WITH MARKINGS TO SHOW CHANGES MADE

In the Claims:

Claims 12 and 13 have been amended as follows:

12. (Amended) A process according to claim 1 ~~or claim 5~~, characterized in that the substrate is a silicon wafer or soda lime glass.

13. (Amended) A process according to claim 1 ~~or claim 5~~, characterized in that the substrate is a compound semiconductor.

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